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Output: solucionariofisisicoquimicamaronandprutton d3ecea30be. tls smoke lesson 2. rar solucionariofisisicoquimicamaronandprutton d3ecea30be. rar solucionariofisisicoquimicamaronandprutton d3ecea30be. rar solucionariofisisicoquimicamaronandprutton d3ecea30be. rar You may want to sort it by the tabular in a different order. [Erythrocyte deformability in patients with essential hypertension treated by diuretic therapy]. Studies in humans and animals have demonstrated that there is alteration in erythrocyte viscosity and erythrocyte deformability. Studies on patients have shown that these alterations may be corrected by changes in the hydration state of the patient. The effect of therapy with diuretics on erythrocyte viscosity and on erythrocyte deformability is controversial. The aim of our study was to evaluate the effect of a diuretic therapy on erythrocyte deformability and to evaluate whether there is a direct correlation between changes in plasma levels of urea, creatinine, beta-2-microglobulin and erythrocyte deformability. We studied 11 normotensive patients, mean age 42.3 +/- 10 years, mean systolic blood pressure 123 +/- 10 mm Hg, and diastolic blood pressure 79 +/- 6 mm Hg. Patients were treated with chlorothiazide and furosemide (Selnid). Before and after the treatment erythrocyte deformability and plasma levels of urea, creatinine and beta-2-microglobulin were studied. Erythrocyte deformability

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